

Fourth Pacific Area Meeting Papers

Symposium on

CLEANING AND MATERIALS PROCESSING FOR ELECTRONICS AND SPACE APPARATUS



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Presented at the
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FOREWORD

The Symposium on Cleaning and Materials Processing for Electronics and Space Apparatus, comprising 6 sessions and 32 papers, was held in Los Angeles, Calif., October 1, 2, and 3, 1962, on the occasion of the Society's Fourth Pacific Area National Meeting. The symposium program was arranged by ASTM Committee F-1 on Materials for Electron Tubes and Semiconductor Devices.¹ Chairman of the symposium committee was D. E. Koontz, Bell Telephone Laboratories, Inc. Assisting Mr. Koontz in developing the program and also serving as session chairmen were V. C. Smith, Barnstead Still and Sterilizer Co.; J. F. Pudvin, Bell Telephone Laboratories, Inc.; R. A. Cotton, Millipore Filter Co; H. E. Powell, Kimble Glass Co.; J. H. Myer, Hughes Aircraft Co.; and A. J. Borofsky, Computer and Data Systems, Anaheim, Calif.²

¹ Name changed in September 1963 to "Materials for Electron Devices and Micro-electronics."

² With Sylvania Electric Products, Inc., at time of this symposium.

NOTE—The Society is not responsible, as a body, for the statements
and opinions advanced in this publication.

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RELATED ASTM PUBLICATIONS

- Compilation of ASTM Standards on Electron Tube Materials (F-1) (1962)
 Materials and Electron Device Processing, STP 300 (1961)
 Cleaning of Electronic Device Components and Materials, STP 246 (1958)

